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Dr. Nicolas Posseme

CEA-Leti, France

Nicolas Posseme received an Engineer degree in Plasma in 2001 from Polytech Orleans, a Ph.D. degree in microelectronics in 2005 for his work on Low k film etching and a HDR degree in 2014.

He joined the CEA-Leti in 2005. First, he joined ST Crolles as CEA-Leti assignee in etch R&D focused in the BEOL. In 2009, he joined IBM Alliance in Albany as Leti assignee to contribute to the development of FDSOI technology. Within Albany state of the art facilities, he worked on device integration to improve the performance of FDSOI devices. In 2011, he moved to AMAT in Sunnyvale as Leti assignee where he worked on the development of disruptive etch processes (FEOL and BEOL). Back in France in 2013, he was deputy head of etch and stripping lab. In 2016, he joined Global Foundries in Dresden as Leti assignee participating in the development of 22FDX and 12FDX technologies as etch and process integration expert. Back in France in 2019, he was head of etch and stripping lab as well as in charge of the engineering (etch and stripping) at Leti. Then he joined beginning 2023 ST Crolles as senior member of technical staff in R&D etch group. He is recently back at CEA-LETI as process integration expert for optical applications.

Nicolas Posseme authored and co-authored over 100 papers and has filed 100 patents. He has also given more than 170 oral presentations at international conferences.